

# ALICE Inner Tracking System (ITS) Upgrade Overview

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# ALICE ITS Upgrade Overview

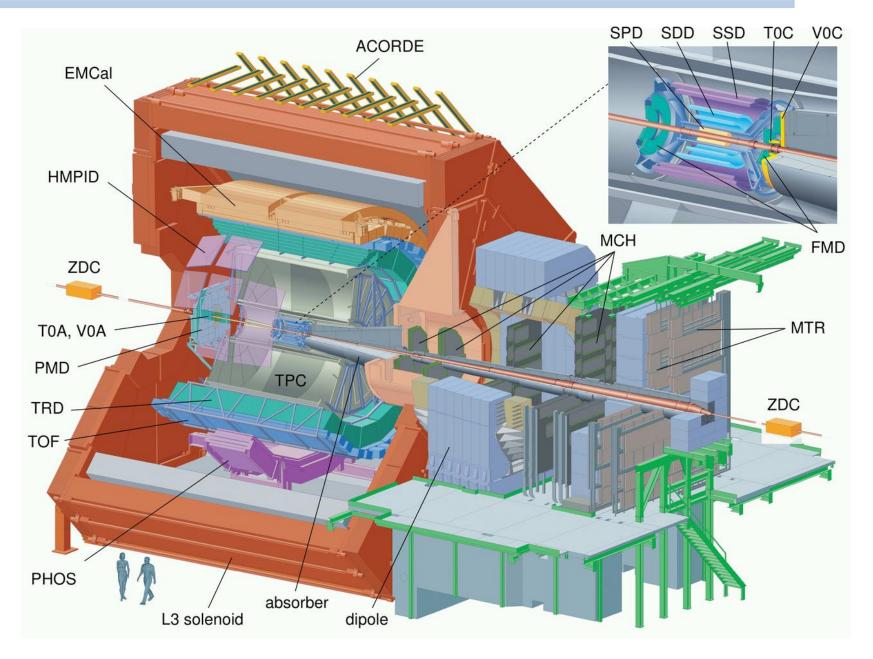
# **Status and Plans**

#### OUTLINE

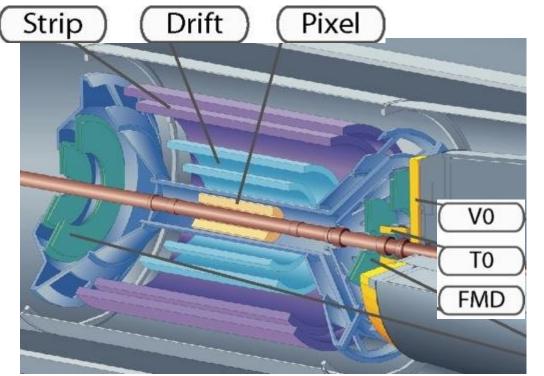
- Upgrade of the ALICE ITS: motivations and specifications
- Layout and main components of the new ITS
- Status and plans
- Conclusions

Disclaimer: this talk is not a comprehensive review of the ITS upgrade but rather focuses on the aspects of the project relevant with Asian contribution

### The Current ALICE Detector



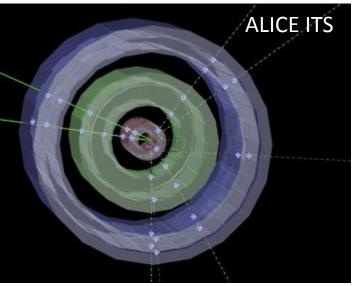
# The Current ALICE Inner Tracking System

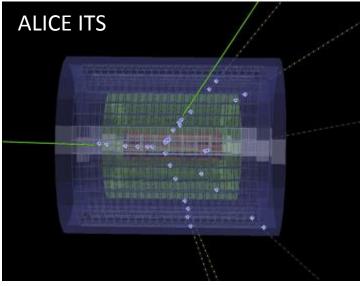


#### Current ITS

6 concentric barrels, 3 different technologies

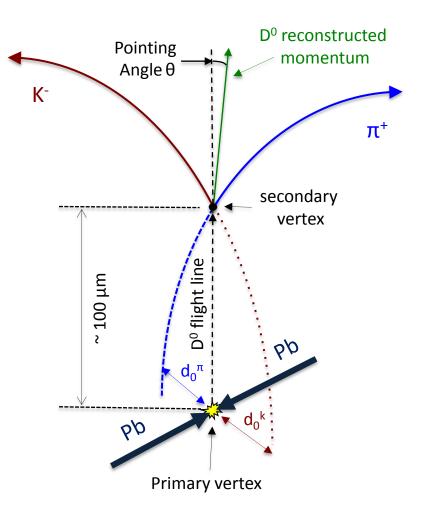
- 2 layers of silicon pixel (SPD)
- 2 layers of silicon drift (SDD)
- 2 layers of silicon strips (SSD)





# Performance – Secondary vertex determination

#### Example: D<sup>0</sup> meson



#### Open charm

Particle	Decay Channel	<b>c</b> τ (μm)	
D <sup>0</sup>	K <sup>-</sup> π <sup>+</sup> (3.8%)	123	
D+	K⁻ π⁺ π⁺ (9.5%)	312	
D <sub>s</sub> +	K⁺ K⁻ π⁺ (5.2%)	150	
$\Lambda_{c}^{\star}$	p K⁻ π⁺ (5.0%)	60	

How precisely is d<sub>0</sub> measured with the current ITS detector?

Analysis based on decay topology and invariant mass technique

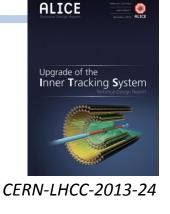
### ALICE ITS Upgrade – Impact parameter resolution

Very good MC description colliding system 600 300  $d_{0,xy}$  resolution ( $\mu m$ )  $d_{0,xy}$  resolution ( $\mu m$ ) ALICE ALICE 500 250 pp  $\sqrt{s} = 7 \text{ TeV}$ charged particles 400 ▲ pp  $\sqrt{s} = 7 \text{ TeV}$ 200  $\bigtriangleup$ data, pions **p**-Pb  $\sqrt{s_{NN}} = 5.02 \text{ TeV}$ data, kaons 300 data, protons • Pb-Pb  $\sqrt{s_{NN}} = 2.76 \text{ TeV}$ 150 MC, pions MC, kaons 200 100 MC, protons 100 50 0 0 0.3 0.4 2 3  $10^{-1}$ 10 1 p<sub>T</sub> (GeV/c)  $p_{\tau}$  (GeV/c) ALICE, Int. J. Mod. Phys. A29 (2014) 1430044 ALICE, Int. J. Mod. Phys. A29 (2014) 1430044

Very weak dependence on the

110 - 120  $\mu$ m at p<sub>T</sub> = 500 MeV/c

- 1. Improve impact parameter resolution by a factor of ~3
- Get closer to IP (position of first layer): 39mm ⇒22mm
- Reduce  $x/X_0$  /layer: ~1.14%  $\Rightarrow$  ~ 0.3% (for inner layers)
- Reduce pixel size: currently 50μm x 425μm 🜩 28μm x 28μm
- 2. Improve tracking efficiency and  $p_T$  resolution at low  $p_T$
- Increase granularity:
  - 6 layers **>** 7 layers
  - silicon drift and strips ➡ pixels
- 3. Fast readout



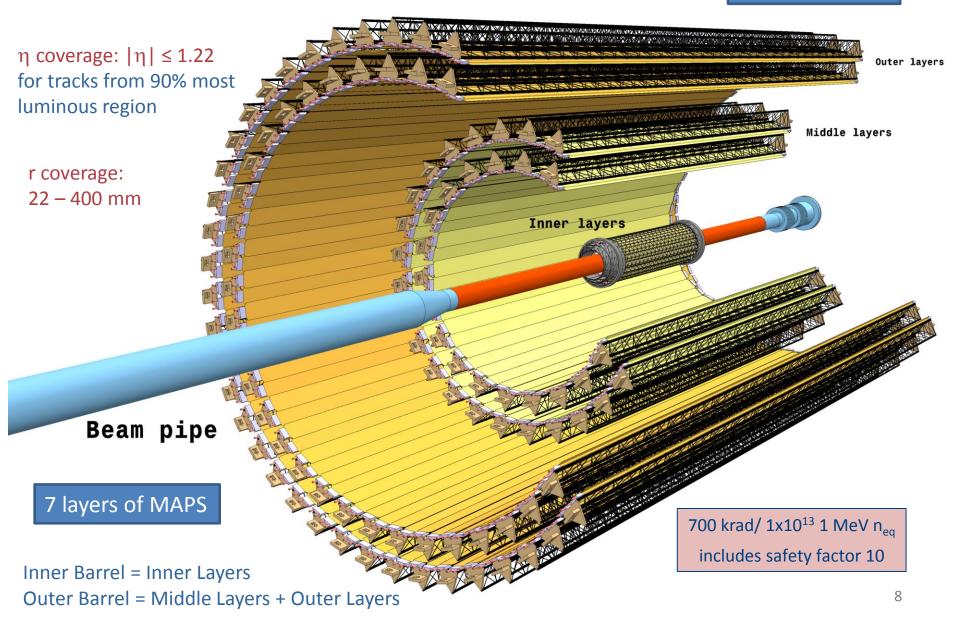


- readout Pb-Pb interactions at > 50 kHz and pp interactions at  $\sim 2 \times 10^5$  Hz (currently limited at 1kHz with full ITS and  $\sim 3$ kHz without silicon drift)
- 4. Fast insertion/removal for yearly maintenance
- possibility to replace non functioning detector modules during yearly shutdown

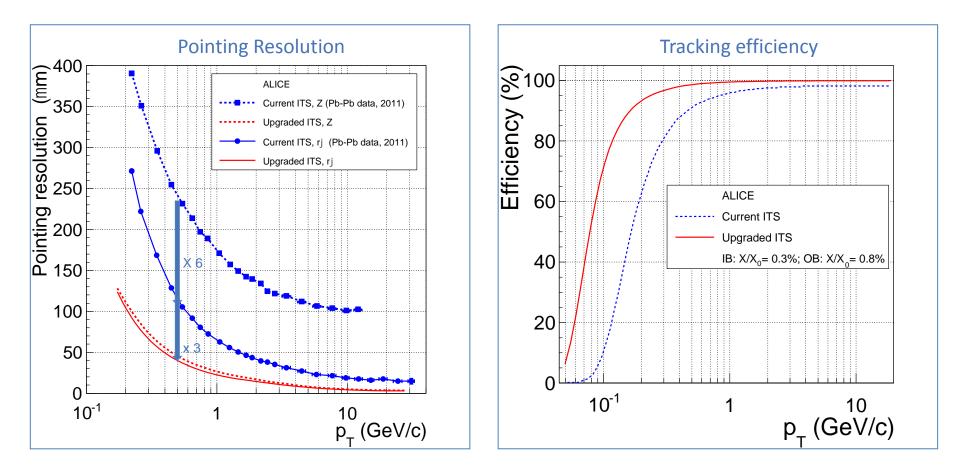
Install detector during LHCC LS2 (2018-19)

### **New ITS Layout**

12.5 G-pixel camera (~10 m<sup>2</sup>)

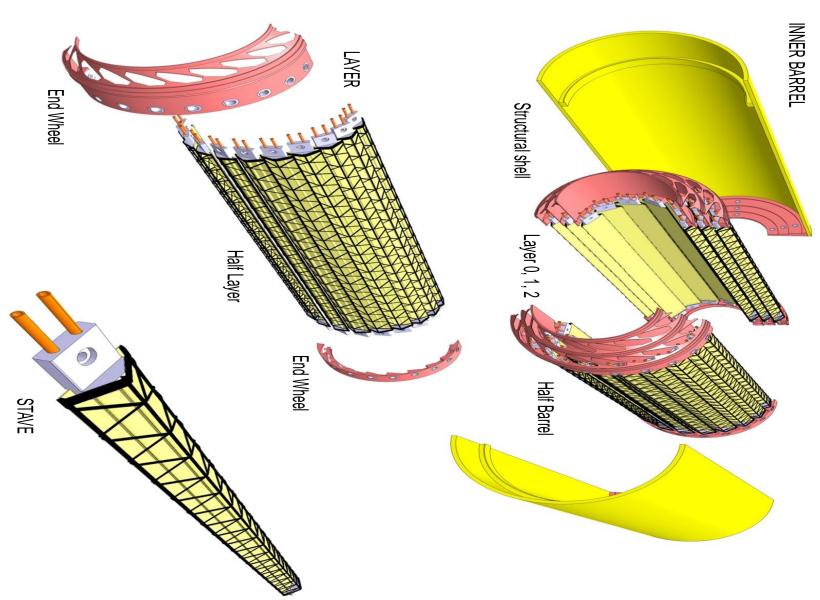


# Performance of new ITS

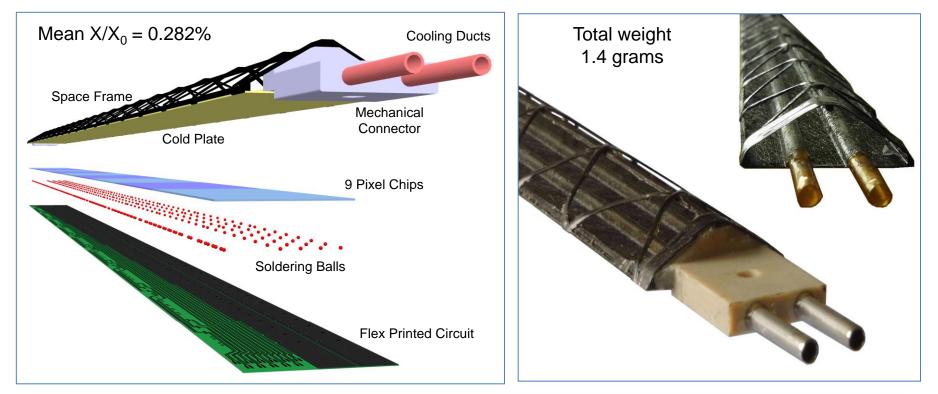


 $\sim$ 40  $\mu$ m at p<sub>T</sub> = 500 MeV/c

### **Inner Barrel**



### New ITS Layout - Inner Barrel



<Radius> (mm): 23,31,39

Nr. of staves: 12, 16, 20

Nr. of chips/layer: 108, 144, 180

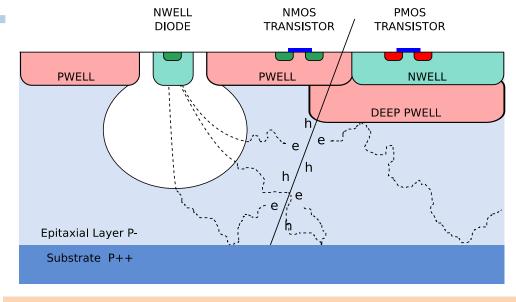
Power density: < 100 mW/cm<sup>2</sup>

Length in z (mm): 270 Nr. of chips/stave: 9 Material thickness: ~ 0.3% X<sub>0</sub> Throughput (@100kHz): < 80 Mb/s×

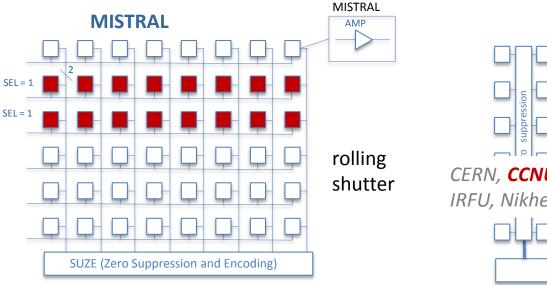
# **PIXEL** Chip

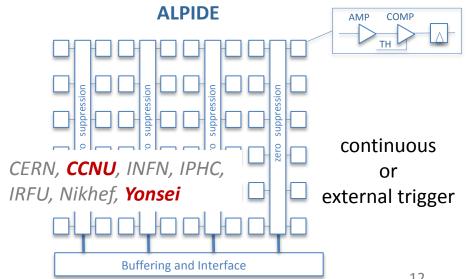
Monolithic PIXEL chip using Tower Jazz CMOS 0.18 µm

- Chip size: 15mm x 30mm
- Pixel pitch  $\sim$  30  $\mu$ m
- Spatial resolution  $\sim$  5  $\mu$ m
- Power density < 100 mW/cm<sup>2</sup>
- Architectures: MISTRAL, ALPIDE



#### Deep p-well allows truly CMOS circuit inside pixel





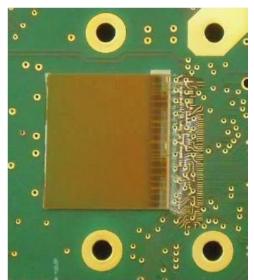
# Pixel Chip - ALPIDE and MISTRAL full-scale prototypes in 2014

MISTRAL FSBB-M0 (Full Scale Building Block Mistral 0)

- About 1/3 of a complete sensor (approx. 9mm x 17mm)
- 416 x 416 pixels of **22μm x 33μm** (final chip **36μm x 62μm**)
- 40μs integration time (final chip ~ 20μs)
- Full chain working (front-end, discr., zero suppression)
- Chips (non irradiated) characterized at SPS

#### ALPIDE Full Scale prototype

- Dimensions: 30mm x 15 mm
- About 0.5 M pixels **28μm x 28μm**
- 40 nW front-end (4.7mW / cm<sup>2</sup>)
- ~40mW/cm<sup>2</sup> total
- Pulse width ~5 μs



#### Figure: Two FSBB M0



Chips characterized at PS, SPS, Frascati

- $\Rightarrow$  Results presented by Magnus
- $\Rightarrow$  Characterization at Korea test beam, analysis ongoing

Figure: picture of pALPIDEfs

#### ALPIDE: baseline solution

- Based on the results obtained in about 8 months of characterization, the current version of ALPIDE (p-ALPIDE1) represents already a suitable solution for the detector construction
- Completion and optimization of the chip via three new iterations

Version	Description	Subm (to TJ)	Delivery	Test
pALPIDE-2	final interface but no HSO	Dec 14	Feb 15	Feb – Jun 15
pALPIDE-3	Pixel FEE optimization, HSO (1.2 Gbit/s), in-pixel multi-event buffer, standard-cell version of matrix readout	Apr 15	Jun 15	Jun - Oct
ALPIDE final	Possible minor improvements	Aug 15	Oct 15	Nov - Jan

- Production (~1400 wafers) starts Feb '16
- Module and stave development programme in 2015 based on ALPIDE prototypes => presentations of Petra, Antonello and Vito

# Pixel chip – plans till production (2/2)

#### MISTRAL-O (optimized for the Outer Barrel): fallback solution

The development of MISTRAL-O will be brought to completion, including the integration in the detector module and stave

- Mature architecture: based on the MIMOSA family
- Pixel pitch  $\sim$ 36µm x 62µm for a power of  $\sim$ 100mW/cm<sup>2</sup>
- The characterization of MISTRAL (22 $\mu m$  x 33 $\mu m$ ) FSBB in 2014 produced good results
- The basic building blocks have been qualified as standalone circuits in '13 and '14

Version	Description	Subm (to TJ)	Delivery	Test
MISTRAL-O	(first) prototype with all final functionalities	June '15	Sep '15	Oct – Dec '15

• Qualification of OB modules and stave based on MISTRAL-O: Jan '15 – Apr '16

# Plans for 2015 (and 2016) – Pixel Chip

#### Production and test of pixel chips

- Procurement of high resistivity silicon wafers (1500 wafers): 2015
- QA of raw silicon wafers (~10% of the total number): Jul '15 Feb '16
  - Verification of physical and electrical properties (measurement of resistivity) => TMEC (Thailand)
- CMOS Manufacturing
  - 4 lots, 340 wafers each: Feb '16 Jun '17 => TowerJazz
- CMOS QA
  - A new lot starts only after the test (wafer probe test) of about 5% of previous lot => Yonsei (Korea) (tbc)
- Ni-Au plating => (e.g. Pactech) market survey and tendering started
- Thinning & Dicing => (mechanical or Laser? ) e.g. Rockwood, Stars
- Chip Test (Electrical, visual) => Yonsei, LIPI (Visual Inspection)

## Plans for 2015 – Module assembly

Construction of Modules and staves for the Inner Barrel and Outer barrel

- Procurement of Module Assembly Machine (MAM) => see Antonello
  - First delivery (CERN): Jun '15
  - Others: (Bari, Liverpool, Pusan, Strasbourg, Wuhan (tbc)): Jan–Jun '16
- Qualification of MAM and assembly procedure at CERN (participation of all teams involved in Module construction): Jul–Sep '15
  - Qualification (acceptance test) of MAM
  - Verification and optimization of assembly procedure
  - Verification and optimization of test procedure

## Plans for 2015 – Readout electronics

#### Readout Electronics: plans for 2015

- Electrical signaling and communication protocol between RU and detector module defined
- Test of data transmission and bit error rate: done in 2014
  - Commercial LVDS transceivers (Nikhef, Prague, Kosice)
- To be done
  - Test communication via high-speed link (400 Mbit/s, 1.2 Gbit/s)
  - Test communication using parallel bus and control lines
    - pALPIDE-3
    - Test system developed by Bari => see Vito
  - Develop an FPGA-based system emulator COMSATS
  - Readout Unit prototype integrating link to CRU and Trigger

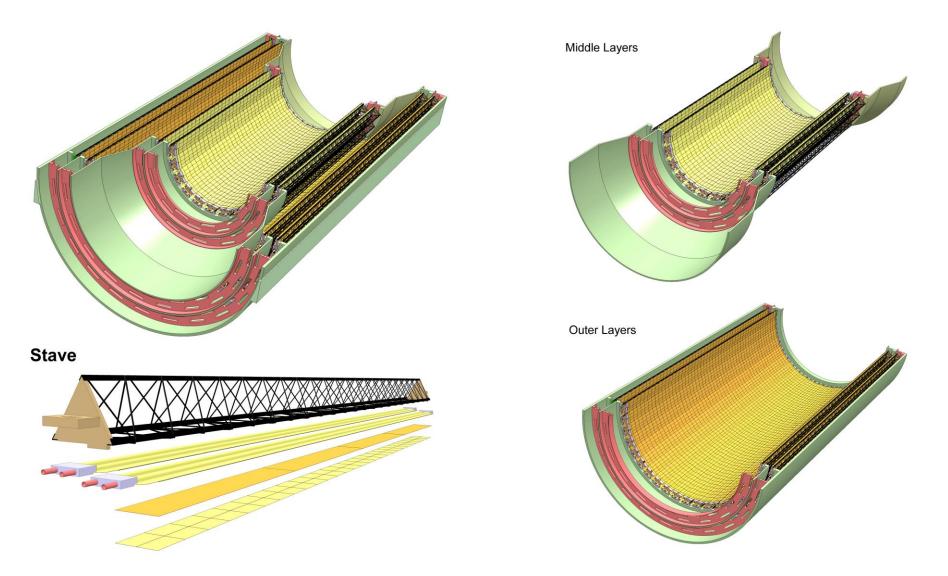
# **Conclusive Remarks**

Important contribution of Asia to many critical aspects of R&D and construction. Some of the activities are well advanced (
), some are ramping-up (), other have not yet started and need to be confirmed/consolidated ()

- China:
  - Pixel chip design, detector and physics simulations
  - OB module construction, readout electronics
- Korea:
  - Pixel chip design, pixel chip characterization, physics simulations
  - Pixel chip mass test, module construction, module construction QA
- Indonesia: Pixel chip mass test QA
- Pakistan: Pixel Chip TCAD simulations, FPGA-based system level simulation of stave readout
- Thailand:
  - Detector simulation, pixel chip characterization, silicon µ-channels
  - QA for CMOS raw wafers, CMOS wafers (laser) dicing

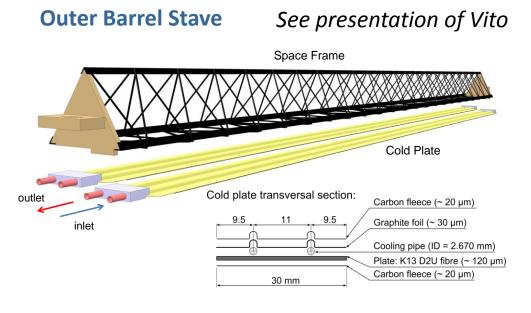
SPARES

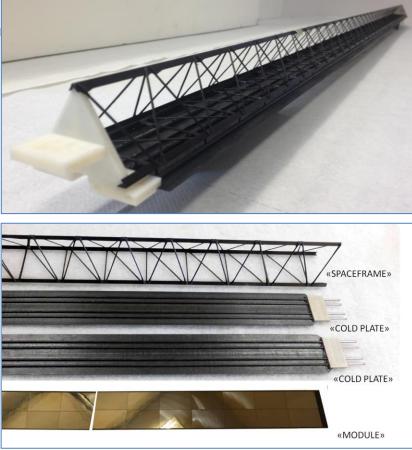
### **Outer Barrel Support Structure and Assembly**



Main structural elements have been prototyped in 2014

# **Outer Barrel**





#### Outer Barrel (OB)

- <radius> (mm): 194, 247, 353, 405
- Nr. staves: 22, 28, 40, 46
- Nr. Chips/layer: (ML), (OL)
- Power density < 100 mW / cm<sup>2</sup>

Length (mm): 843 (ML), 1475 (OL) Nr. modules/stave: 4 (ML), 7 (OL) Material thickness:  $\sim 0.8\% X_0$ Throughput (@100kHz): < 3Mb/s × cm<sup>-2</sup>

# Readout – general scheme and data throughput

